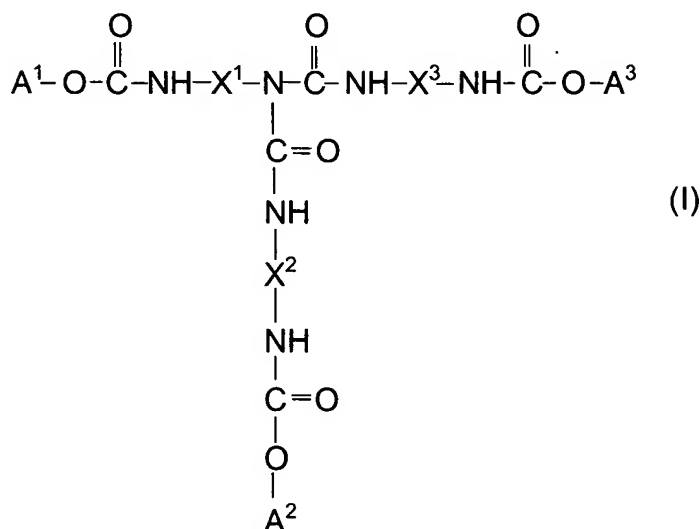


Amendments to the Claims

1 – 13. Cancelled

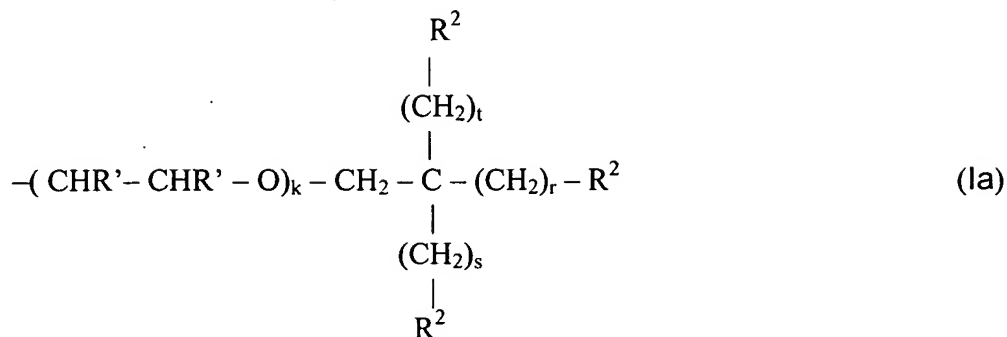
14 (New). A radiation-sensitive element comprising

- (a) an optionally pretreated substrate;
- (b) a radiation-sensitive coating comprising
 - (i) at least one photoinitiator or sensitizer, which is capable of absorbing radiation of a wavelength in the range of 250 to 1,200 nm;
 - (ii) at least one oligomer A of formula (I)

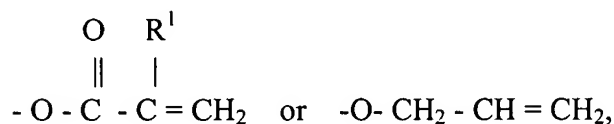


wherein X^1 , X^2 and X^3 are independently $C_2 - C_{18}$ alkanediyl or $C_6 - C_{20}$ arylene,
 A^1 , A^2 and A^3 are independently

$-(\text{CHR}' - \text{CHR}' - \text{O})_k - \text{CH}_2 - \text{CH} = \text{CH}_2$ or a fragment represented by formula
1a



wherein k is an integer from 0 to 10, each R' is independently a hydrogen atom or CH₃, each R² is independently a hydrogen atom,

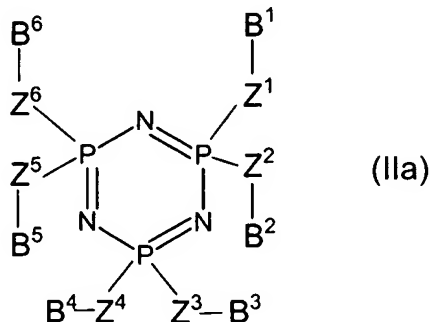
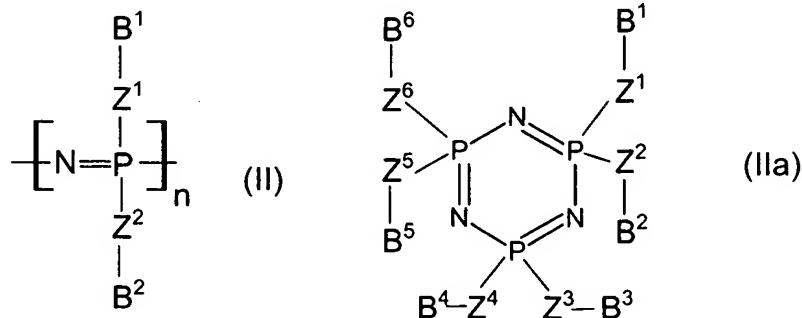


R¹ is a hydrogen atom or C₁ – C₁₂ alkyl and

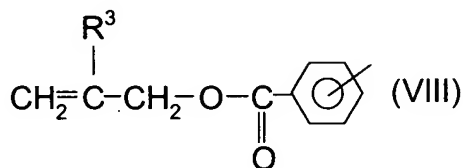
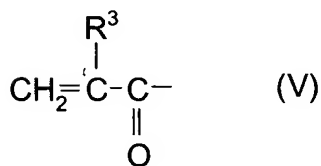
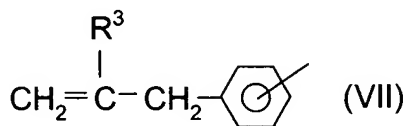
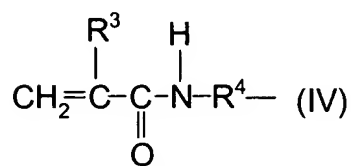
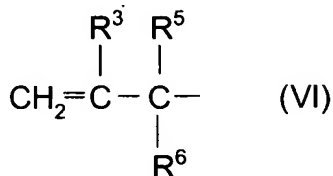
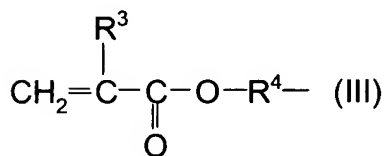
r, s and t independently are 0 or 1,

with the proviso that in each fragment A¹, A² and A³ at least one R² is not a hydrogen atom if A¹, A² and A³ are all a fragment represented by formula (1a), and

(iii) at least one oligomer B, which is a phosphazene, represented by formulas (II) or (IIa):



wherein Z^1 , Z^2 , Z^3 , Z^4 , Z^5 and Z^6 are independently $-O-$ or $-NR-$, R is a hydrogen atom or $C_1 - C_{12}$ alkyl, n is greater than 3 and B^1 , B^2 , B^3 , B^4 , B^5 and B^6 are fragments represented by formulas (III) – (VIII)



wherein R^3 is a hydrogen atom or $C_1 - C_{12}$ alkyl, R^4 is $C_2 - C_{12}$ alkanediyl and R^5 and R^6 are independently a hydrogen atom or $C_1 - C_{12}$ alkyl; and

- (c) optionally, at least one additive comprising coinitiators which form free radicals after the excitation of the initiator or sensitizer with radiation of a wavelength of 250 to 1,200 nm, binders, thermopolymerization inhibitors, dyes, plasticizers, chain transfer agents, leuco dyes, inorganic fillers or surfactants.

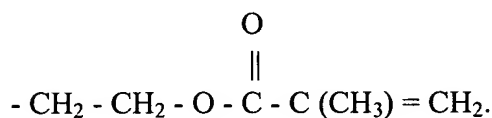
15 (New). The radiation-sensitive element according to claim 14, wherein X^1 , X^2 and X^3 are the same in oligomer A.

16 (New). The radiation-sensitive element according to claim 15, wherein X^1 , X^2 and X^3 are hexamethylene.

17 (New). The radiation-sensitive element according to claim 14 , wherein oligomer B is a phophazene represented by formula (IIa).

18 (New). The radiation-sensitive element according to claim 14 , wherein oligomer A is the reaction product of hexamethylene diisocyanate biuret and at least one acrylate of a multi-valent alcohol comprising at least one hydroxyl group, and oligomer B is represented by formula (IIa) wherein each

B^1, B^2, B^3, B^4, B^5 and B^6 are



19 (New). The radiation-sensitive element according to claim 14, wherein an oxygen-impermeable overcoat is provided on top of the radiation-sensitive coating.

20 (New). The radiation-sensitive element according to claim 14, wherein the substrate is an aluminum foil or plate that has optionally been subjected to at least one pretreatment comprising roughening, anodizing or applying a hydrophilizing layer.

21 (New). A process for the production of an imaged element comprising

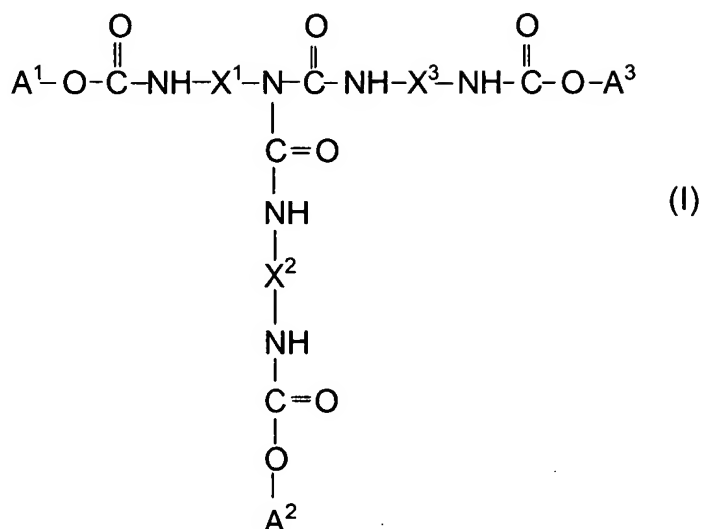
(a) providing a radiation-sensitive element

(1) an optionally pretreated substrate and

(2) a radiation-sensitive coating comprising

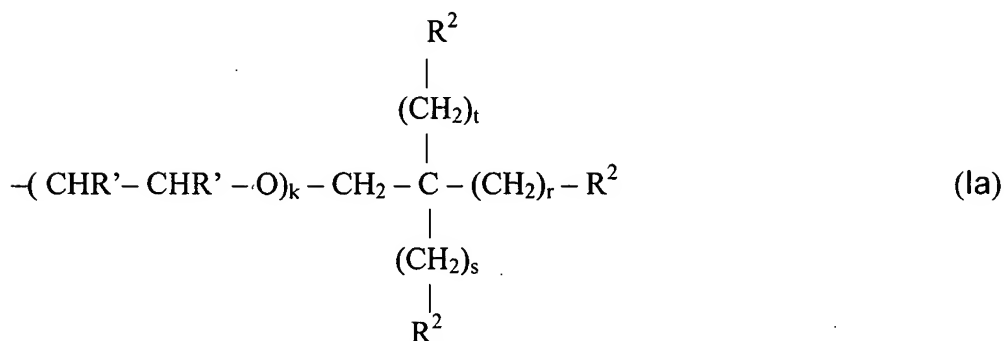
(i) at least one photoinitiator or sensitizer, which is capable of absorbing radiation of a wavelength in the range of 250 to 1,200 nm;

(ii) at least one oligomer A of formula (I)

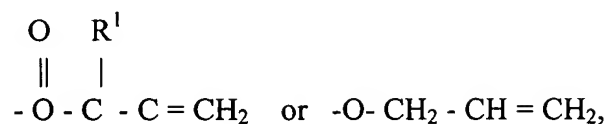


wherein X^1 , X^2 and X^3 are independently $\text{C}_2 - \text{C}_{18}$ alkanediyl or $\text{C}_6 - \text{C}_{20}$ arylene,
 A^1 , A^2 and A^3 are independently

$-(\text{CHR}'-\text{CHR}'-\text{O})_k-\text{CH}_2-\text{CH}=\text{CH}_2$ or a fragment represented by formula
la



wherein k is an integer from 0 to 10, each R' is independently a hydrogen atom or CH_3 , each R^2 is independently a hydrogen atom,

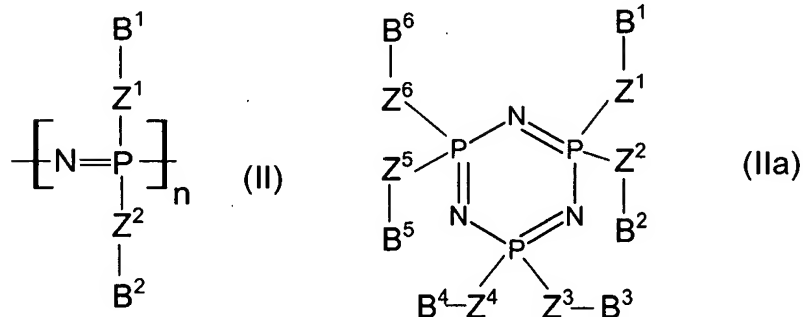


R^1 is a hydrogen atom or $\text{C}_1 - \text{C}_{12}$ alkyl and

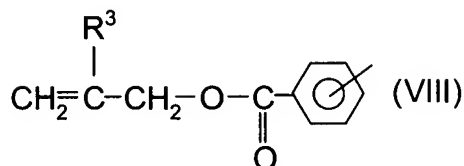
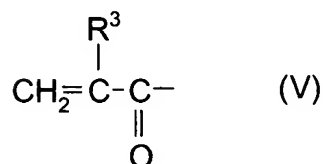
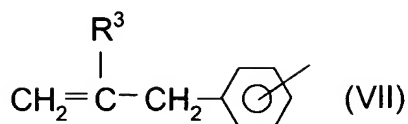
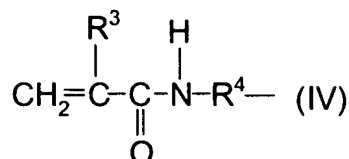
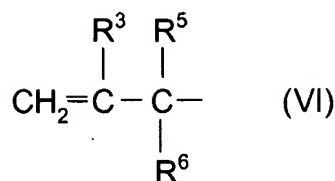
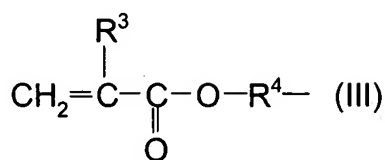
r, s and t independently are 0 or 1,

with the proviso that in each fragment A^1, A^2 and A^3 at least one R^2 is not a hydrogen atom if A^1, A^2 and A^3 are all fragments represented by formula (Ia), and

(iii) at least one oligomer B, which is a phosphazene represented by formulas (II) or (IIa):



wherein $\text{Z}^1, \text{Z}^2, \text{Z}^3, \text{Z}^4, \text{Z}^5$ and Z^6 are independently $-\text{O}-$ or $-\text{NR}-$, R is a hydrogen atom or $\text{C}_1 - \text{C}_{12}$ alkyl, n is greater than 3 and $\text{B}^1, \text{B}^2, \text{B}^3, \text{B}^4, \text{B}^5$ and B^6 are fragments represented by formulas (III) – (VIII)

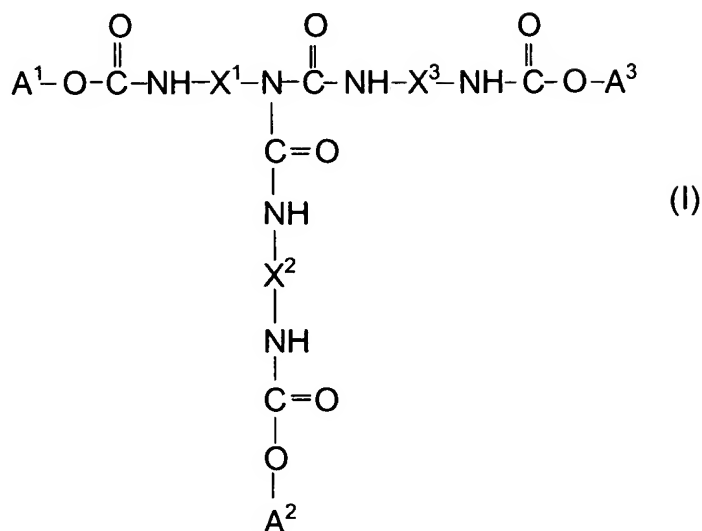


wherein R^3 is a hydrogen atom or $\text{C}_1 - \text{C}_{12}$ alkyl, R^4 is $\text{C}_2 - \text{C}_{12}$ alkanediyl and R^5 and R^6 are independently a hydrogen atom or $\text{C}_1 - \text{C}_{12}$ alkyl;

- (b) image-wise irradiation of the radiation-sensitive element with radiation of a wavelength adjusted to the absorber contained in the radiation-sensitive coating of the element;
- (c) optionally heating the image-wise irradiated element;
- (d) removing the non-irradiated areas with an aqueous alkaline developer to provide the imaged element; and
- (e) optionally heating the imaged element obtained in step (d) or subjecting it to overall exposure or both.

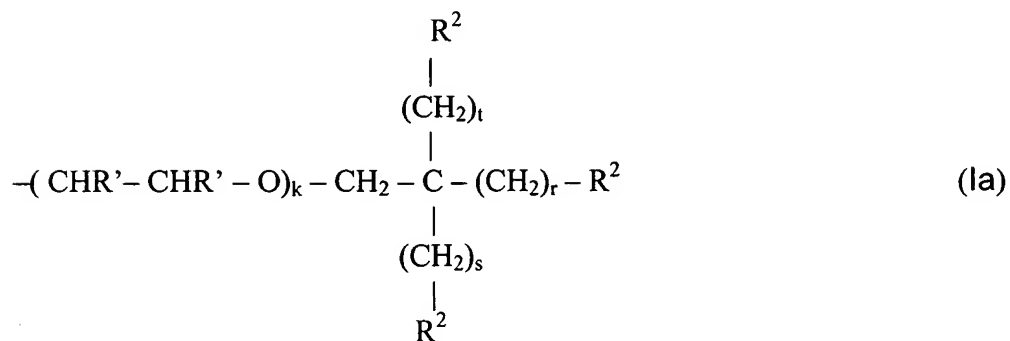
22 (New). A radiation-sensitive composition comprising

- (i) at least one photoinitiator or sensitizer, which is capable of absorbing radiation of a wavelength in the range of 250 to 1,200 nm;
- (ii) at least one oligomer A of formula (I)

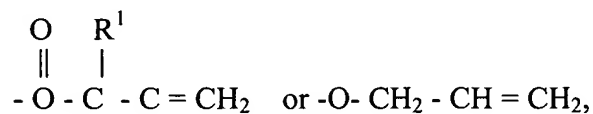


wherein X^1 , X^2 and X^3 are independently $\text{C}_2 - \text{C}_{18}$ alkanediyl or $\text{C}_6 - \text{C}_{20}$ arylene,
 A^1 , A^2 and A^3 are independently

$-(\text{CHR}' - \text{CHR}' - \text{O})_k - \text{CH}_2 - \text{CH} = \text{CH}_2$ or a fragment represented by formula
1a



wherein k is an integer from 0 to 10, each R' is independently a hydrogen atom or CH_3 , each R^2 is independently a hydrogen atom,

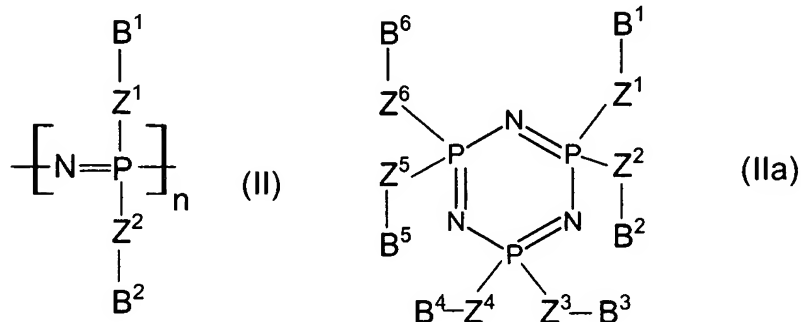


R^1 is a hydrogen atom or $\text{C}_1 - \text{C}_{12}$ alkyl and

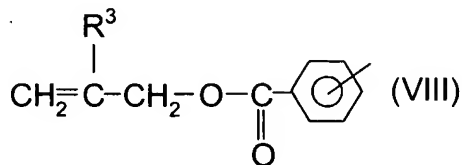
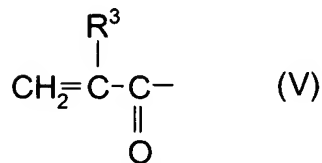
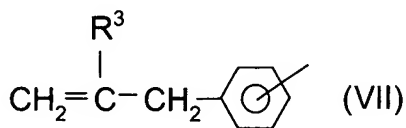
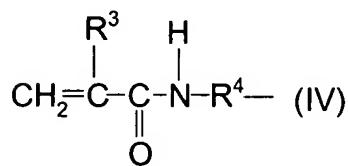
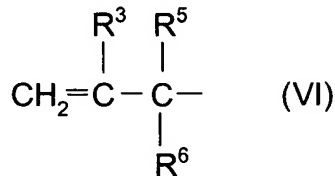
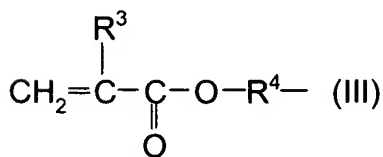
r, s and t independently are 0 or 1,

with the proviso that in each fragment A^1 , A^2 and A^3 at least one R^2 is not a hydrogen atom if A^1 , A^2 and A^3 are all fragments represented by formula (Ia), and

(iii) at least one oligomer B, which is a phosphazene represented by formulas (II) or (IIa):



wherein Z^1 , Z^2 , Z^3 , Z^4 , Z^5 and Z^6 are independently $-O-$ or $-NR-$, R is a hydrogen atom or $C_1 - C_{12}$ alkyl, n is greater than 3 and B^1 , B^2 , B^3 , B^4 , B^5 and B^6 are fragments represented by formulas (III) – (VIII)



wherein R^3 is a hydrogen atom or $C_1 - C_{12}$ alkyl, R^4 is $C_1 - C_{12}$ alkanediyl and R^5 and R^6 are independently a hydrogen atom or $C_1 - C_{12}$ alkyl; and

(iv) a solvent or solvent mixture; and

(v) optionally at least one additive comprising coinitiators which form free radicals after the excitation of the photoinitiator or sensitizer with radiation of a wavelength of 250 to 1,200 nm, binders, thermopolymerization inhibitors, dyes, plasticizers, chain transfer agents, leuco dyes, inorganic fillers or surfactants.

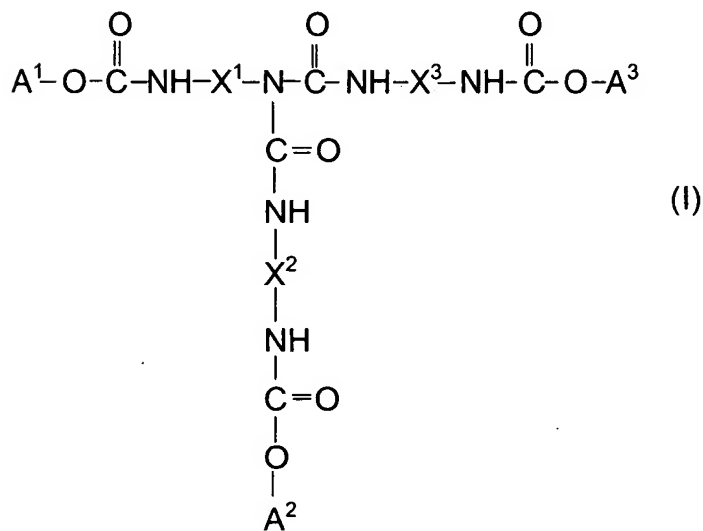
23 (New). A process for the production of a radiation-sensitive element comprising the steps of:

(a) providing an optionally pretreated substrate;

(b) applying a radiation-sensitive composition comprising:

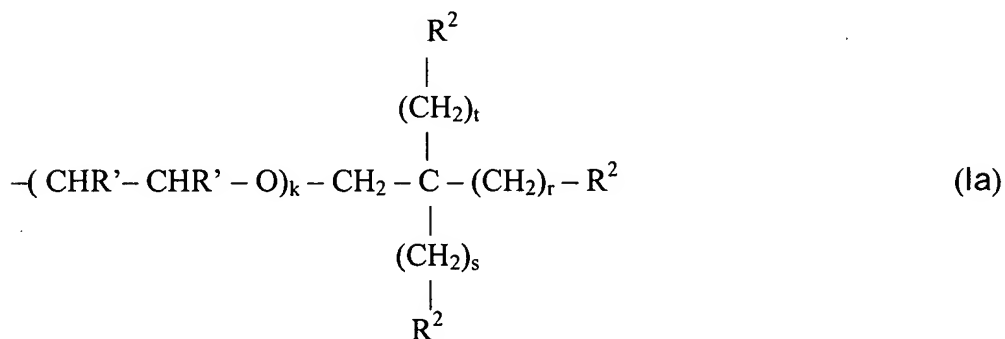
(1) at least one photoinitiator and sensitizer, which is capable of absorbing radiation of a wavelength in the range of 250 to 1,200 nm;

(2) at least one oligomer A of formula (I)

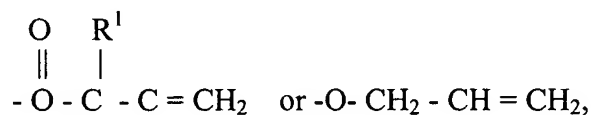


wherein X^1 , X^2 and X^3 are independently $C_2 - C_{18}$ alkanediyl or
 $C_6 - C_{20}$ arylene,
 A^1 , A^2 and A^3 are independently

$-(CHR' - CHR' - O)_k - CH_2 - CH = CH_2$ or a fragment represented by formula
1a



wherein k is an integer from 0 to 10, each R' is independently a hydrogen atom or CH_3 , each R^2 is independently a hydrogen atom,

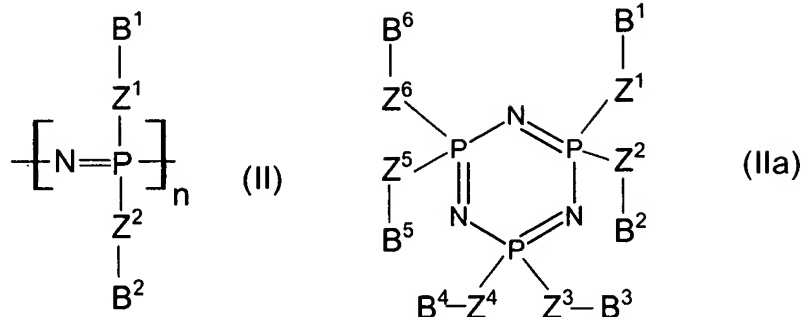


R^1 is a hydrogen atom or $C_1 - C_{12}$ alkyl and

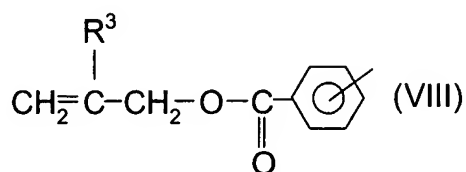
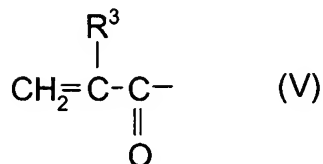
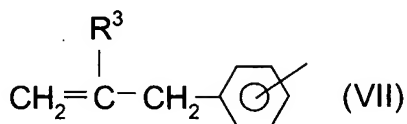
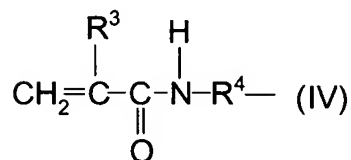
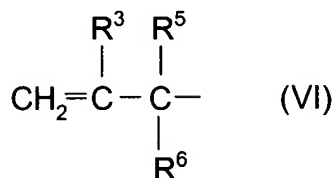
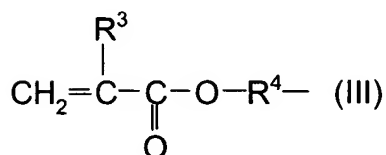
r , s and t independently are 0 or 1,

with the proviso that in each fragment A^1 , A^2 and A^3 at least one R^2 is not a hydrogen atom if A^1 , A^2 and A^3 are all fragments represented by formula (1a), and

(3) at least one oligomer B, which is a phosphazene represented by formulas (II) or (IIa):



wherein $\text{Z}^1, \text{Z}^2, \text{Z}^3, \text{Z}^4, \text{Z}^5$ and Z^6 are independently $-\text{O}-$ or $-\text{NR}-$, R is a hydrogen atom or $\text{C}_1 - \text{C}_{12}$ alkyl, n is greater than 3 and $\text{B}^1, \text{B}^2, \text{B}^3, \text{B}^4, \text{B}^5$ and B^6 are represented by formulas (III) – (VIII)



wherein R^3 is a hydrogen atom or $\text{C}_1 - \text{C}_{12}$ alkyl, R^4 is $\text{C}_1 - \text{C}_{12}$ alkanediyl and R^5 and R^6 are independently a hydrogen atom or $\text{C}_1 - \text{C}_{12}$ alkyl; and

- (4) a solvent or solvent mixture;
- (c) drying; and
- (d) optionally applying an oxygen-impermeable overcoat and drying.